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12/792,470 2 June 2010 (02.06.2010) US(71) Applicant (for all designated States except US): **MKS INSTRUMENTS, INC.** [US/US]; 2 Tech Drive, Suite 201, Andover, MA 01810 (US).

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(54) Title: DEVICES, SYSTEMS, AND METHODS FOR CARBONATION OF DEIONIZED WATER

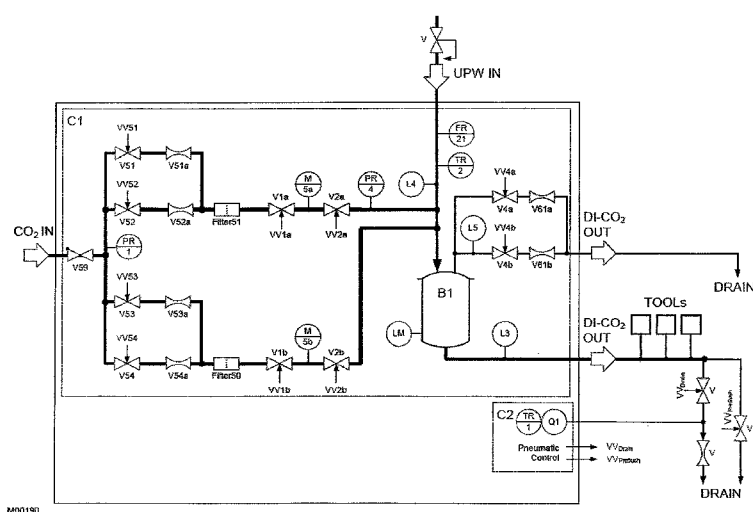


FIG. 11

(57) Abstract: Devices, systems, and methods employed in wet cleaning semiconductor devices are provided. In particular, systems that can deliver deionized water with the desired concentration of CO₂ and methods of generating deionized water with a desired concentration of CO₂ for use in wet cleaning of semiconductor devices are provided.